



# 6 INCH CONDUCTIVE

## SIC Substrate Specification

Grade	Zero MPD Production Grade (Z Grade)	Dummy Grade (D Grade)
Diameter	149.5 mm ~ 150.0 mm	149.5 mm ~ 150.0 mm
Poly-type	4H	4H
Thickness	350 $\mu\text{m}$ $\pm$ 15 $\mu\text{m}$	350 $\mu\text{m}$ $\pm$ 25 $\mu\text{m}$
Wafer Orientation	Off axis : 4.0° toward $\langle 11\bar{2}0 \rangle \pm 0.5^\circ$	Off axis : 4.0° toward $\langle 11\bar{2}0 \rangle \pm 0.5^\circ$
Micropipe Density	$\leq 0.2 \text{ cm}^{-2}$	$\leq 15 \text{ cm}^{-2}$
Resistivity	0.015 ~ 0.024 $\Omega\cdot\text{cm}$	0.015 ~ 0.028 $\Omega\cdot\text{cm}$
Primary Flat Orientation	{10-10} $\pm 5.0^\circ$	{10-10} $\pm 5.0^\circ$
Primary Flat Length	47.5 mm $\pm$ 2.0 mm	47.5 mm $\pm$ 2.0 mm
Edge Exclusion	3 mm	3 mm
LTV / TTV / Bow / Warp	$\leq 2.5 \mu\text{m}$ / $\leq 6 \mu\text{m}$ / $\leq 25 \mu\text{m}$ / $\leq 35 \mu\text{m}$	$\leq 5 \mu\text{m}$ / $\leq 15 \mu\text{m}$ / $\leq 40 \mu\text{m}$ / $\leq 60 \mu\text{m}$
Roughness	Polish Ra $\leq 1 \text{ nm}$	Polish Ra $\leq 1 \text{ nm}$
	CMP Ra $\leq 0.2 \text{ nm}$	CMP Ra $\leq 0.5 \text{ nm}$
Edge Cracks By High Intensity Light	—	Cumulative length $\leq 20 \text{ mm}$ single length $\leq 2 \text{ mm}$
Hex Plates By High Intensity Light	Cumulative area $\leq 0.05\%$	Cumulative area $\leq 0.1\%$
Polytype Areas By High Intensity Light	—	Cumulative area $\leq 3\%$
Visual Carbon Inclusions	Cumulative area $\leq 0.05\%$	Cumulative area $\leq 3\%$
Silicon Surface Scratches By High Intensity Light	—	Cumulative length $\leq 1 \times$ wafer diameter
Edge Chips High By Intensity Light	None permitted $\geq 0.2 \text{ mm}$ width and depth	7 allowed, $\leq 1 \text{ mm}$ each
Threading Screw Dislocation	$\leq 500 \text{ cm}^{-2}$	—
Silicon Surface Contamination By High Intensity Light	—	—
Packaging	Multi-wafer Cassette Or Single Wafer Container	Multi-wafer Cassette Or Single Wafer Container